

L Number	Hits	Search Text	DB	Time stamp
1	756	photoresist\$4 same (bubble or shell)	USPAT; US-PGPUB	2003/07/25 10:23
2	115	(photoresist\$4 same (bubble or shell))	USPAT;	2003/07/25
3	38	and electron and microscop\$2	US-PGPUB	10:23
		((photoresist\$4 same (bubble or shell))	USPAT;	2003/07/25
		and electron and microscop\$2) and	US-PGPUB	10:35
		(flood\$3 or inspect\$4)		
4	2104	250/310	USPAT;	2003/07/25
5	1646	250/311	US-PGPUB	10:35
			USPAT;	2003/07/25
6	2446	250/306	US-PGPUB	10:35
			USPAT;	2003/07/25
7	2044	250/307	US-PGPUB	10:35
			USPAT;	2003/07/25
8	393	(250/310 or 250/311 or 250/306 or	US-PGPUB	10:36
		250/307) and photoresist\$4	USPAT;	2003/07/25
9	338	((250/310 or 250/311 or 250/306 or	US-PGPUB	11:17
		250/307) and photoresist\$4) and layer	USPAT;	2003/07/25
10	82	((((250/310 or 250/311 or 250/306 or	US-PGPUB	11:17
		250/307) and photoresist\$4) and layer)	USPAT;	2003/07/25
		and electron and inspect\$4	US-PGPUB	11:17
11	79	((((250/310 or 250/311 or 250/306 or	USPAT;	2003/07/25
		250/307) and photoresist\$4) and layer)	US-PGPUB	11:18
		and electron and inspect\$4) and		
		microscop\$2		
12	11	(US-6143666-\$ or US-5783366-\$ or	USPAT	2003/07/25
		US-6444381-\$ or US-5510216-\$ or		11:15
		US-6420702-\$ or US-6589709-\$ or		
		US-6358670-\$ or US-5928821-\$ or		
		US-5242864-\$ or US-6121130-\$ or		
		US-5747803-\$).did.		
13	148	430/16	USPAT	2003/07/25
				11:15
14	512	430/23	USPAT	2003/07/25
				11:15
15	1939	430/30	USPAT	2003/07/25
				11:15
16	1898	430/296	USPAT	2003/07/25
				11:16
17	3011	430/311	USPAT	2003/07/25
				11:16
18	984	438/623	USPAT	2003/07/25
				11:16
19	637	438/701	USPAT	2003/07/25
				11:16
20	823	438/725	USPAT	2003/07/25
				11:16
21	4652	(430/16 or 430/23 or 430/30 or 430/296 or	USPAT;	2003/07/25
		430/311 or 438/623 or 438/701 or 438/725)	US-PGPUB	11:17
		and photoresist\$4		
22	4311	((430/16 or 430/23 or 430/30 or 430/296	USPAT;	2003/07/25
		or 430/311 or 438/623 or 438/701 or	US-PGPUB	11:17
		438/725) and photoresist\$4) and layer		
23	304	((((430/16 or 430/23 or 430/30 or 430/296	USPAT;	2003/07/25
		or 430/311 or 438/623 or 438/701 or	US-PGPUB	11:18
		438/725) and photoresist\$4) and layer)		
		and electron and inspect\$4		
24	149	(((((430/16 or 430/23 or 430/30 or 430/296	USPAT;	2003/07/25
		or 430/311 or 438/623 or 438/701 or	US-PGPUB	11:18
		438/725) and photoresist\$4) and layer)		
		and electron and inspect\$4) and		
		microscop\$2		
25	13	(((((430/16 or 430/23 or 430/30 or	USPAT;	2003/07/25
		430/296 or 430/311 or 438/623 or 438/701	US-PGPUB	11:18
		or 438/725) and photoresist\$4) and layer)		
		and electron and inspect\$4) and		
		microscop\$2) and flood\$3		

-	5579	inspect\$4 and (Electron adj microscop\$4)	USPAT; US-PGPUB	2003/07/23 17:30
-	5944	inspect\$4 and (Electron adj microscop\$4)	USPAT; US-PGPUB; EPO;	2003/07/23 13:19
-	4132	((inspect\$4 and (Electron adj microscop\$4)) and layer\$3	DERWENT USPAT; US-PGPUB; EPO;	2003/07/23 13:20
-	427	((inspect\$4 and (Electron adj microscop\$4)) and layer\$3) and untreat\$3 and treat\$4	DERWENT USPAT; US-PGPUB; EPO;	2003/07/23 15:32
-	0	"09820143"	DERWENT USPAT; US-PGPUB; EPO;	2003/07/23 13:26
-	52	((inspect\$4 and (Electron adj microscop\$4)) and layer\$3) and untreat\$3 and treat\$4) and photoresist\$3	DERWENT USPAT; US-PGPUB; EPO;	2003/07/23 15:42
-	728	((inspect\$4 and (Electron adj microscop\$4)) and layer\$3) and ((untreat\$3 and treat\$4) or (expos\$3 and unexpos\$3) or (radiat\$3 and unradiat\$3))	DERWENT USPAT; US-PGPUB; EPO;	2003/07/23 15:34
-	579	((inspect\$4 and (Electron adj microscop\$4)) and layer\$3) and ((untreat\$3 same treat\$4) or (expos\$3 same unexpos\$3) or (radiat\$3 same unradiat\$3))	DERWENT USPAT; US-PGPUB; EPO;	2003/07/23 15:34
-	159	((inspect\$4 and (Electron adj microscop\$4)) and layer\$3) and ((untreat\$3 same treat\$4) or (expos\$3 same unexpos\$3) or (radiat\$3 same unradiat\$3)) and photoresist\$3	DERWENT USPAT; US-PGPUB; EPO;	2003/07/23 15:58
-	26	((inspect\$4 and (Electron adj microscop\$4)) and layer\$3) and ((untreat\$3 same treat\$4) or (expos\$3 same unexpos\$3) or (radiat\$3 same unradiat\$3)) and photoresist\$3 and flood\$3	DERWENT USPAT; US-PGPUB; EPO;	2003/07/24 08:59
-	18	okoroanyanwu.in.	DERWENT USPAT; US-PGPUB; EPO;	2003/07/23 17:29
-	160	singh-bhanwar.in.	DERWENT USPAT; US-PGPUB; EPO;	2003/07/23 17:29
-	0	acheta-aldden.in.	DERWENT USPAT; US-PGPUB; EPO;	2003/07/23 17:29
-	35	(okoroanyanwu.in. or singh-bhanwar.in.) and (Electron adj microscop\$4)	DERWENT USPAT; US-PGPUB	2003/07/23 17:30
-	1	((okoroanyanwu.in. or singh-bhanwar.in.) and (Electron adj microscop\$4)) and untreat\$3	USPAT; US-PGPUB	2003/07/23 17:30
-	676	layer\$3 and flood\$3 and photoresist\$3 and (integrat\$3 adj circuit\$3)	USPAT; US-PGPUB; EPO;	2003/07/24 10:38
-	511	(layer\$3 and flood\$3 and photoresist\$3 and (integrat\$3 adj circuit\$3)) and region	DERWENT USPAT; US-PGPUB; EPO;	2003/07/24 10:38
-	442	((layer\$3 and flood\$3 and photoresist\$3 and (integrat\$3 adj circuit\$3)) and region) and reduc\$5	DERWENT USPAT; US-PGPUB; EPO;	2003/07/24 10:40

-	20	((layer\$3 and flood\$3 and photoresist\$3 and (integrat\$3 adj circuit\$3)) and region) and reduc\$5) and shell	USPAT; US-PGPUB; EPO; DERWENT	2003/07/24 11:10
-	88	((layer\$3 and flood\$3 and photoresist\$3 and (integrat\$3 adj circuit\$3)) and region) and reduc\$5) and inspec\$5	USPAT; US-PGPUB; EPO; DERWENT	2003/07/24 11:16
-	40	((layer\$3 and flood\$3 and photoresist\$3 and (integrat\$3 adj circuit\$3)) and region) and reduc\$5) and inspec\$5) and enclos\$3	USPAT; US-PGPUB; EPO; DERWENT	2003/07/24 12:28
-	266052	inspect\$4 amd electron and (electron adj microscop\$2) and (integrated adj circuit)	USPAT; US-PGPUB; EPO; DERWENT	2003/07/24 12:38
-	10485	(inspect\$4 amd electron and (electron adj microscop\$2) and (integrated adj circuit)) and layer and surface and transform\$	USPAT; US-PGPUB; EPO; DERWENT	2003/07/24 12:44
-	624	((inspect\$4 amd electron and (electron adj microscop\$2) and (integrated adj circuit)) and layer and surface and transform\$) and ((enclos\$3 or encapsulat\$3) near4 (surface or layer))	USPAT; US-PGPUB; EPO; DERWENT	2003/07/24 12:45
-	45	((inspect\$4 amd electron and (electron adj microscop\$2) and (integrated adj circuit)) and layer and surface and transform\$) and ((enclos\$3 or encapsulat\$3) near4 (surface or layer))) and photoresist	USPAT; US-PGPUB; EPO; DERWENT	2003/07/24 12:45
-	52	((inspect\$4 amd electron and (electron adj microscop\$2) and (integrated adj circuit)) and layer and surface and transform\$) and ((enclos\$3 or encapsulat\$3) near4 (surface or layer))) and photoresist\$3	USPAT; US-PGPUB; EPO; DERWENT	2003/07/24 15:01
-	527	(shell or (cross adj link\$4)) and (barrier or trap\$4) and layer and outgas\$4	USPAT; US-PGPUB; EPO; DERWENT	2003/07/24 15:03
-	47	((shell or (cross adj link\$4)) and (barrier or trap\$4) and layer and outgas\$4) and photoresist\$4	USPAT; US-PGPUB; EPO; DERWENT	2003/07/24 15:07
-	2	5330881.pn.	USPAT; US-PGPUB; EPO; DERWENT	2003/07/24 15:07
-	811	inspect\$3 and (integrat\$3 adj circuit) and (electron adj microscop\$2) and electron and beam	USPAT; US-PGPUB	2003/07/25 08:41
-	181	(inspect\$3 and (integrat\$3 adj circuit) and (electron adj microscop\$2) and electron and beam) and ((treat\$4 or transform\$5) same surface)	USPAT; US-PGPUB	2003/07/25 08:42
-	12	(inspect\$3 and (integrat\$3 adj circuit) and (electron adj microscop\$2) and electron and beam) and ((treat\$4 or transform\$5) same surface same ("SEM" or microscop\$2) same inspect\$4)	USPAT; US-PGPUB	2003/07/25 08:43
-	12	((inspect\$3 and (integrat\$3 adj circuit) and (electron adj microscop\$2) and electron and beam) and ((treat\$4 or transform\$5) same surface)) and ((treat\$4 or transform\$5) same surface same ("SEM" or microscop\$2) same inspect\$4)	USPAT; US-PGPUB	2003/07/25 10:22